

Application No. 10/517,320  
Amendment dated: October 30, 2006  
Reply to OA of: June 28, 2006

**Amendments to the specification:**

Please insert the following as the first line in the specification:

--The present application is the U.S. Phase of International Application No. PCT/ EP98/06047 and which claims benefit under 35 U.S.C. 119(e) of application 60/389,497 filed June 19, 2002.--

Please replace the paragraph beginning at page 8, line 4 with the following rewritten paragraph:

--Silicon wafers were cleaned in TL2 (MilliQ MILLIQ™purified deionized water:25% hydrogen peroxide:37% hydrogen chloride 6:1:1 at 85°C for 10min) and rinsed thoroughly in MilliQ MILLIQ™purified deionized water and dried in nitrogen gas prior to coating of 25Å of titanium and 2000Å of gold by electron beam evaporation. The equipment used was a Balzers UMS 500 P system. The evaporation rate was 1Å/s and 10Å/s for titanium and gold, respectively. A base pressure of at least  $10^{-9}$  was kept and during evaporation the pressure was noted to be on the low  $10^{-7}$  scale at all times. This type of surfaces was used for all experiments except SPR and QCM measurements. The SPR surfaces (plain gold) were obtained from Biacore AB, Uppsala, Sweden and the gold-coated QCM crystals were obtained from Biosensor Applications Sweden. It should be noted that the surfaces used for SPR experiments had a similar surface roughness compared to the ones used for the rest of the experiments, whereas the surface coating of the QCM crystals were of a much rougher nature.--

Please replace the paragraph beginning at page 8, line 16 with the following rewritten paragraph:

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--Before exposure to thiol loading solutions the sample surfaces were cleaned in TL1 (MilliQ MILLIQ™purified deionized water:25% hydrogen peroxide:30% ammonia 5:1:1 at 85°C for 10min) and rinsed thoroughly in MilliQ MILLIQ™purified deionized water. The concentration of thiols in the 99.5% ethanol based loading solutions was 20µM for pure thiol solutions as well as for mixed thiol solutions. Incubation of the surfaces occurred during approximately 40h at room conditions. The samples were rinsed in 99.5% ethanol twice and then ultrasonicated for 3min (since the gold coating on the QCM crystals did not withstand this step, it was omitted) and rinsed two more times in 99.5% ethanol. If not stated otherwise, the surfaces were stored in pure 99.5% ethanol for a maximum of 8h before they were dried in nitrogen gas and analysed. A number of samples examined with IRAS and null ellipsometry were also subsequently incubated at room conditions for 30min in ABTNT at a concentration of 0.02g/L, prepared in PBS (pH7.4) and examined again. At all time the samples were handled with TL1-cleaned forceps.--